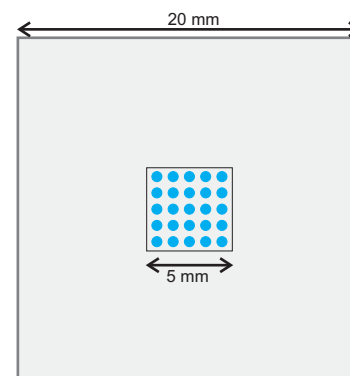


STANDARD E-BEAM MADE NANOIMPRINT TEMPLATES

Standard e-beam made molds are provided on 20x20mm² Si substrates. They offer combination of high-resolution and large enough area of 5x5mm² for most uses at an affordable price. These templates are normally on stock and available for shipment.

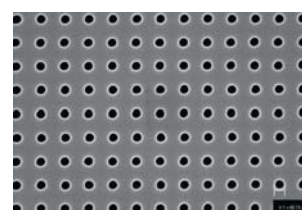
- Magnetic nanostructures
- LED Light extraction layers, photovoltaic patterning
- Templates for crystal growth
- Nanoimprint process development
- Photonic / plasmonic structures



Layout of the standard ebeam-made molds

Holes on Square Lattice

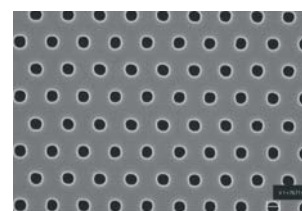
Product	Period	Area	Feature Diameter / Height
P100s_h_5w5	100nm	5x5mm ²	50nm / 100nm
P150s_h_5w5	150nm	5x5mm ²	60nm / 100nm
P200s_h_5w5	200nm	5x5mm ²	70nm / 100nm



Square hole array - 150nm pitch

Holes on Hexagonal Lattice

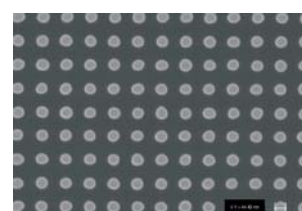
Product	Period	Area	Feature Diameter / Height
P200h_h_5w5	200nm	5x5mm ²	80nm / 100nm
P300h_h_5w5	300nm	5x5mm ²	125nm / 100nm
P400h_h_5w5	400nm	5x5mm ²	150nm / 100nm



Hexagonal hole array - 200nm pitch

Pillars on Square Lattice

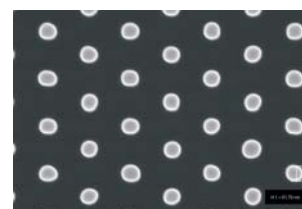
Product	Period	Area	Feature Diameter / Height
P100s_p_5w5	100nm	5x5mm ²	50nm / 100nm
P150s_p_5w5	150nm	5x5mm ²	60nm / 100nm
P200s_p_5w5	200nm	5x5mm ²	80nm / 100nm



Square pillar array - 100nm pitch

Pillars on Hexagonal Lattice

Product	Period	Area	Feature Diameter / Height
P200h_p_5w5	200nm	5x5mm ²	70nm / 100nm
P300h_p_5w5	300nm	5x5mm ²	110nm / 100nm
P400h_p_5w5	400nm	5x5mm ²	120nm / 100nm



Hexagonal pillar array - 200nm pitch

* Feature size / height may vary from batch to batch. Inquire for available stock

* Anti-adhesion coating available as an option